

**IN THE SPECIFICATION:**

The specification as amended below with replacement paragraphs shows added text with underlining and deleted text with ~~striketrough~~.

Please REPLACE paragraph [0007] on page 2 with the following amended paragraph:

**[0007]** Such a photolithographic method can be used before an organic film is formed, but causes a problem when it is used after an organic film is formed. Because the organic film is very susceptible to damage from water, it must be thoroughly isolated from water while being fabricated, and even after the fabrication. Moreover, the photolithographic method includes an exposure to water during the ~~peeling-off~~ peeling-off and etching of the resist, so it is not suitable for the organic film and the cathode electrode layer.